

Title (en)

GRINDING WHEEL, GRINDING SYSTEM AND METHOD FOR GRINDING A BLADE

Title (de)

SCHLEIFSCHEIBE, SCHLEIFSYSTEM UND VERFAHREN ZUM SCHLEIFEN EINES MESSERS

Title (fr)

MEULE, SYSTEME D'AFFUTAGE ET PROCEDE POUR AFFUTER UNE LAME

Publication

EP 1187701 B1 20030122 (DE)

Application

EP 00929535 A 20000517

Priority

- DE 19928022 A 19990618
- DE 10003707 A 20000128
- EP 0004450 W 20000517

Abstract (en)

[origin: US6726542B1] The invention relates to a grinding wheel for grinding a blade, on the surface of which ions are deposited by means of a plasma-supported method and containing silicon carbide as abrasive medium with a grain size ranging from 100 to 500 mesh, said material being deposited in a ceramic based binding agent with aluminum silicate. The abrasive medium grains are thermally hardened and bonded in the porous aluminum silicate bond. Abrasive medium concentration in the grinding wheel is higher than 1 volume %. Said grinding wheel is used in a grinding system for rough grinding the blade. Polishing is then carried out with a second grinding wheel containing pure corundum as abrasive medium with a grain size ranging from 400 to 800 mesh, which is deposited in a multicomponent synthetic resin, preferably a phenol resin based resin with a concentration of more than 1 volume %, preferably 30 to 50%. The abrasive medium contains polishing-active filling materials with a volume fraction ranging between 3% and 10%.

IPC 1-7

B24D 3/18; B24D 3/28; B24D 3/34; B24D 5/02; B24B 3/54

IPC 8 full level

B24B 3/54 (2006.01); **B24B 3/36** (2006.01); **B24D 3/00** (2006.01); **B24D 3/02** (2006.01); **B24D 3/34** (2006.01); **B24D 7/18** (2006.01)

CPC (source: EP US)

B24B 3/36 (2013.01 - EP US); **B24D 3/02** (2013.01 - EP US); **B24D 3/34** (2013.01 - EP US); **B24D 7/18** (2013.01 - EP US)

Designated contracting state (EPC)

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

DOCDB simple family (publication)

US 6726542 B1 20040427; AT E231427 T1 20030215; CA 2375216 A1 20001228; EP 1187701 A1 20020320; EP 1187701 B1 20030122; JP 2003502164 A 20030121; WO 0078505 A1 20001228

DOCDB simple family (application)

US 1863302 A 20020110; AT 00929535 T 20000517; CA 2375216 A 20000517; EP 0004450 W 20000517; EP 00929535 A 20000517; JP 2001504542 A 20000517